

(19) World Intellectual Property  
Organization  
International Bureau



(43) International Publication Date  
24 March 2005 (24.03.2005)

PCT

(10) International Publication Number  
**WO 2005/026843 A3**

(51) International Patent Classification<sup>7</sup>: **G03F 7/20**

(21) International Application Number:  
PCT/EP2004/010188

(22) International Filing Date:  
13 September 2004 (13.09.2004)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:  
10343333.3 12 September 2003 (12.09.2003) DE  
10 2004 010571.5 26 February 2004 (26.02.2004) DE

(71) Applicant (for all designated States except US): **CARL ZEISS SMT AG** [DE/DE]; Carl-Zeiss-Strasse 22, 73447 Oberkochen (DE).

(72) Inventors; and

(75) Inventors/Applicants (for US only): **KÖHLER, Jess** [DE/DE]; Kretzergang 6a, 88090 Immenstaad (DE).  
**WANGLER, Johannes** [DE/DE]; An der Reute 15, 89551

Königsbronn (DE). **BROTSACK, Markus** [DE/DE]; Gartenstrasse 44, 73430 Aalen (DE). **SINGER, Wolfgang** [DE/DE]; Egerlandstrasse 45, 73432 Aalen (DE). **FIOLOKA, Damian** [DE/DE]; Heckenrosenweg 36, 73447 Oberkochen (DE). **MAUL, Manfred** [DE/DE]; Elchweg 29, 73434 Aalen (DE).

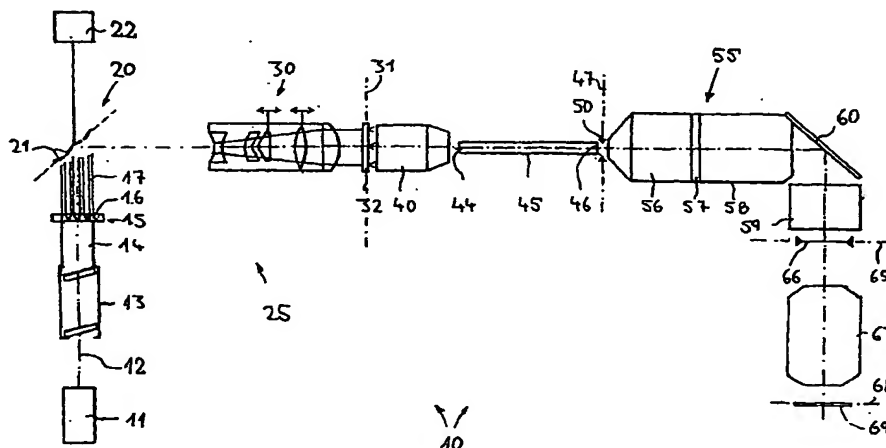
(74) Agent: **RUFF, WILHELM, BEIER, DAUSTER & PARTNER**; Kronenstrasse 30, 70174 Stuttgart (DE).

(81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.

(84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI,

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(54) Title: **ILLUMINATION SYSTEM FOR A MICROLITHOGRAPHY PROJECTION EXPOSURE INSTALLATION**



(57) Abstract: An illumination system for a microlithography projection exposure installation is used to illuminate an illumination field with the light from a primary light source (11). The illumination system has a light distribution device (25) which receives light from the primary light source and, from this light, produces a two-dimensional intensity distribution which can be set variably in a pupil-shaping surface (31) of the illumination system. The light distribution device has at least one optical modulation device (20) having a two-dimensional array of individual elements (21) that can be controlled individually in order to change the angular distribution of the light incident on the optical modulation device. The device permits the variable setting of extremely different illuminating modes without replacing optical components.



FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI,  
SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ,  
GW, ML, MR, NE, SN, TD, TG).

(88) Date of publication of the international search report:  
26 May 2005

**Published:**

- with international search report
- before the expiration of the time limit for amending the claims and to be republished in the event of receipt of amendments

*For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.*